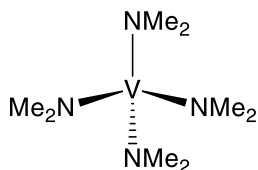


Catalog # 23-0500 Tetrakis(dimethylamino)vanadium(IV), min. 95% TDMAV
 Syn: [V\(dma\)4](#)



Thermal Behavior:

- Melting point: 50-60°C [1]
- Distillation: 50-60°C/10⁻² Torr [1], Vaporization: 70°C [2]
- Decomposition: >190°C [2]
- Vapor pressure: 1 Torr/64°C [3]
- TGA diagram and data is available in [2]

Technical Notes:

1. ALD/CVD precursor for vanadium thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
VO _x	ALD ALD	RT RT	0.3 Torr -	O ₃ H ₂ O	50-200°C 50-200°C	2 2, 4-5
VN	CVD PEALD	RT 85°C	10 mTorr 0.36 Torr	NH ₃ ^{PL} N ₂	250-300°C 150-300°C	6 7
VSe ₂	CVD	-	AP	^t Bu ₂ Se	250-500°C	8
Hf _{1-x} V _x B _y	CVD	RT	-	Hf(BH ₄) ₄	220°C	9

References:

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